

ABSTRACT

5 A photomask blank having a film of at least one layer
formed on a substrate is manufactured by forming a film on a
substrate and irradiating the film with light from a flash
lamp. A photomask is manufactured from the thus manufactured
photomask blank by forming a patterned resist on the film on
the blank by photolithography, etching away those portions of
10 the film which are not covered with the resist, and removing
the resist. The photomask blank and photomask have minimized
warpage and improved chemical resistance.